

## IN THE CLAIMS

1 (Currently Amended).      A method comprising:

- forming a pore in an insulator;
- ~~forming a heater in said pore by filling said pore with a conductive material and then removing the upper portion of said conductive material;~~
- ~~filling the upper portion with a phase change material that extends over said insulator;~~
- ~~forming a substantially planar upper surface of said phase change material; and~~
- ~~forming a substantially planar upper electrode over said substantially planar upper surface of said phase change material.~~
- forming a sidewall spacer in said pore;
- forming a heater in said pore with said sidewall spacer;
- removing an upper portion of said heater to form a gap;
- filling the gap with a phase change material that extends over said insulator;
- patterning and etching said phase change material over said insulator.

Claims 2 and 3 (Canceled).

4 (Previously Presented).      The method of claim 1 including planarizing the upper surface of said insulator.

Claims 5, 6, and 7 (Canceled).

8 (Currently Amended).      The method of claim [[7]] 1 including forming a T-shaped phase change material.

9 (Currently Amended).      The method of claim [[3]] 1 including forming a sidewall spacer in said pore.

10 (Currently Amended). The method of claim 9 ~~including~~ wherein forming a heater  
includes depositing metal in said pore after forming said sidewall spacer.

Claims 11-31 (Canceled).